

TECHNICAL SPEC FOR Track system

System Model:

TEL Clean Track MkVz

Tool status :

The tool, inclusive photoresist pumps, and the bypack units have been flushed and cleaned with solvent/DI water, and dry cleaned with CCA. The solvent lines (HMDS, Resist, thinner, developer have been disconnected from the tool), as well as the electric power supply lines. The bypacks of the tool are situated in the basement under the fab. The water cooling line and signal cables are still connected between process unit and bypack. Decommissioning was done by trained Litho technicians.

Specific Model: MD625256

Wafer size: 6 inch

Wafer type: Jeida flat

Wafer flow:

Number coater/developer modules: 1C/2D

inLine system: Yes

Resists / Coaters: 2 (mini + iwaki)

E2 Develop nozzle kits: 2

RRC Pumps & kits:

Dual-stream nozzles / Developer: no

Solvent & developer auto supply systems: Yes

Temperature / Humidity controller: Yes

Configuration/layout of each block:

GEM: yes

AVG:

HMDS Bubblers: Venturi

Power supply: 208 V, 3 Phase, AC Transformer:

Vintage: 1995

Missing parts: none

Defected parts: none

Operating system:

<u>Machine</u>	COATER 3
<u>S.N. :</u>	MD625256
<u>Manufacturing date</u>	Jan-95
<u>Machine soft type</u>	Mk VZ
<u>ARDiMuS</u>	OK
<u>Main Controller</u>	MK50.191
<u>Process Block1</u>	MZ0D021T.00
<u>Process Block2</u>	MZ0D021T.00
<u>Process Block3</u>	MZ0D021T.00
<u>Process Block 4</u>	MZ0D021T.00
<u>Controller type/model</u>	FC-9801F model 1
<u>Disk</u>	I/O data Silicon disk
<u>Floppy drive</u>	External Logitec LFD-331

